

L Number	Hits	Search Text	DB	Time stamp
2	15940	430/5,311,313,314,316,317.ccls. 438/296,424,427,692,697.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/24 11:14
3	121075	silicon adj nitride "si.sub.3 n.sub.4" si3n4 sixny "si.sub.x n.sub.y"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 11:15
4	272236	oxide near (region layer coating material film)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 11:15
5	44673	planariz\$5 planaris\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 11:16
6	43406	cmp (((chemical\$3 adj mechanical\$3) (chemical\$3-mechanical\$3)) adj polish\$3) chemical\$3-mechanical\$3-polish\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 11:16
8	46117	active near region	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 11:17
1	456	CHEN-COMING-.in. WU-JUAN-YUAN-.in. WU-J-Y-.in. LUR-WATER-.in. LUR-W-.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/24 11:17
9	12559	sti! (shallow adj trench adj isolation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 11:19
10	1318	(430/5,311,313,314,316,317.ccls. 438/296,424,427,692,697.ccls.) and (sti! (shallow adj trench adj isolation))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 11:35
11	701	(active near region) near2 small\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 12:08
12	712	(active near region) near2 larg\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 12:08
13	77533	trench	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 11:36
7	23	partial adj reverse adj2 (mask active photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 11:42
16	75	(reverse near2 (mask active photoresist)) same (sti! (shallow adj trench adj isolation))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 11:45
17	58	((reverse near2 (mask active photoresist)) same (sti! (shallow adj trench adj isolation))) not (partial adj reverse adj2 (mask active photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 11:45
18	446	(active near region) near2 narrow\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 12:08
19	1364	(active near region) near2 wid\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 12:08

21	10	(silicon adj nitride "si.sub.3 n.sub.4" si3n4 sixny "si.sub.x n.sub.y") same (oxide near (region layer coating material film)) same ((planariz\$5 planaris\$5) (cmp (((chemical\$3 adj mechanical\$3) (chemical\$3-mechanical\$3)) adj polish\$3) chemical\$3-mechanical\$3-polish\$3)) same trench same (((active near region) near2 small\$2) ((active near region) near2 narrow\$2)) same (((active near region) near2 larg\$2) ((active near region) near2 wid\$2))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 12:20
22	8	(("6043133") or ("6194287") or ("5498565") or ("20030129808")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 12:23
23	2	("6486040").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 12:45
25	8	(("5792707") or ("5837612") or ("5854133") or ("5858842")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 13:00
26	2	("6004863").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/24 13:19